## PATENT ABSTRACTS OF JAPAN

(11)Publication number:

09-199419

(43) Date of publication of application: 31.07.1997

(51)Int.CI.

H01L 21/20 C30B 29/38 H01L 33/00 H01S 3/18

(21)Application number: 08-007340

(71)Applicant: NEC CORP

(22)Date of filing:

19.01.1996

(72)Inventor: NIDOU MASAAKI

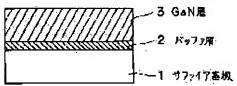
KIMURA AKITAKA SUNAKAWA HARUO YAMAGUCHI ATSUSHI

## (54) CRYSTAL GROWTH METHOD OF GALLIUM NITRIDE COMPOUND SEMICONDUCTOR AND MANUFACTURE OF SEMICONDUCTOR LASER

## (57)Abstract:

PROBLEM TO BE SOLVED: To improve the flatness and the orientational property of crystallization, and to decrease the defect of lamination by a method wherein the surface of a crystal substrate is formed in such a manner that the tilt angle of the plane direction, which is equivalent to specific plane direction, is set within a prescribed value.

SOLUTION: A GaN buffer layer 2 is crystal–grown on a sapphire substrate 1 having (1, -1, 0, 1) faces as the surface, and a GaN layer 3 is crystal–grown thereon. The crystal growth speed in the direction vertical to the (1, -1, 0, 1) faces is slow, and the atomic migration on the above–mentioned plane is intensified. As a result, a hexagonal gallium nitride compound semiconductor, which is smooth on the surface in the direction in parallel with the substrate surface and having uniform C-axial orientational direction, is formed. The same effect can be obtained even when the orientation of substrate is inclined by 5 degrees or less from the (1, -1, 0, 1) face orientation.



## **LEGAL STATUS**

[Date of request for examination]

19.01.1996

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

2830814

[Date of registration]

25.09.1998

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2000 Japan Patent Office